



Atomic Layer Deposition of Thin-Films

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Message from the Guest Editors

Dear Colleagues,

Atomic layer deposition (ALD) is a thin film deposition technique based on sequential surface reactions of gas phase precursors and reactants. Currently, ALD is adopted as an essential process in the fabrication of microelectronic devices, and its applications toward controlled synthesis of various nanomaterials are expanding. Several techniques related to ALD are also emerging, such as atomic layer etching (ALE), area-selective atomic layer deposition (AS-ALD), and molecular layer deposition (MLD). Fundamental aspects of ALD, such as surface chemistry and nucleation theory, still demand further research.

The topics of interest of this Special Issue include, but are not limited to:

- Deposition of thin films by ALD
- Atomic layer etching (ALE)
- Area-selective ALD (AS-ALD)
- Molecular layer deposition (MLD)
- Applications of ALD materials
- Applications of ALD processes
- Fundamental aspects of ALD





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Message from the Editorial Board

Now more than ever, research is asked to deliver knowledge and technologies to solve the major challenges faced by our society. The development of new materials and devices for (without the ambition to be exhaustive) energy, health and food technology, together with the need for establishing processes that reduce the impact on critical resources and the environment, is indeed in the spotlight of most contemporary research. Surface science and engineering play a key role in this regard, with an incredible potential in delivering new and deep scientific understanding and technical solutions essential to solve most of the major societal challenges.

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